

6 first and second stages, one of which is for scanningly
7 moving the original and the other of which is for scanningly
8 moving the substrate;

9 measuring means for measuring a relative deviation
10 between said first stage and said second stage in a
11 predetermined direction other than the direction of scanning
12 movement; and

13 adjusting means for adjusting positional relationship
14 between the first stage and the second stage on the basis of
15 the measurement by said measuring means.--

1 --170. An exposure method for the manufacture of
2 microdevices, in which a portion of a pattern of an original
3 is projected onto a substrate and in which the original and
4 the substrate are scanned in a timed relation such that the
5 pattern of the original is transferred to the substrate,
6 said method comprising the steps of:

7 providing first and second stages, one of which is for
8 scanningly moving the original and the other of which is for
9 scanningly moving the substrate;

10 measuring a relative deviation between the first stage
11 and the second stage in a predetermined direction other than
12 the scanning movement direction; and

13 adjusting positional relationship between the first
14 stage and the second stage on the basis of the measurement
15 in said measuring step.--